

Members' Profiles

Shineisha Co. Ltd.

1. Business Summary

Shineisha has specialized in the manufacturing of photomasks since 1963. By manufacturing photomasks over these last 46 years under the corporate philosophy "Meet the needs of our customers promptly and with 100% satisfaction," we have done our best to make some contribution to the semiconductor industry. Our clientele includes university research institutes, corporate R&D institutes, and electronics companies.

After becoming a supporting member of the Micromachine Center in March 2009, Shineisha participated in the Exhibition Micromachine/MEMS held in July of the same year with an exhibit on ultraprecision photomasks for MEMS. The company remains committed to developing superior products with no equal.

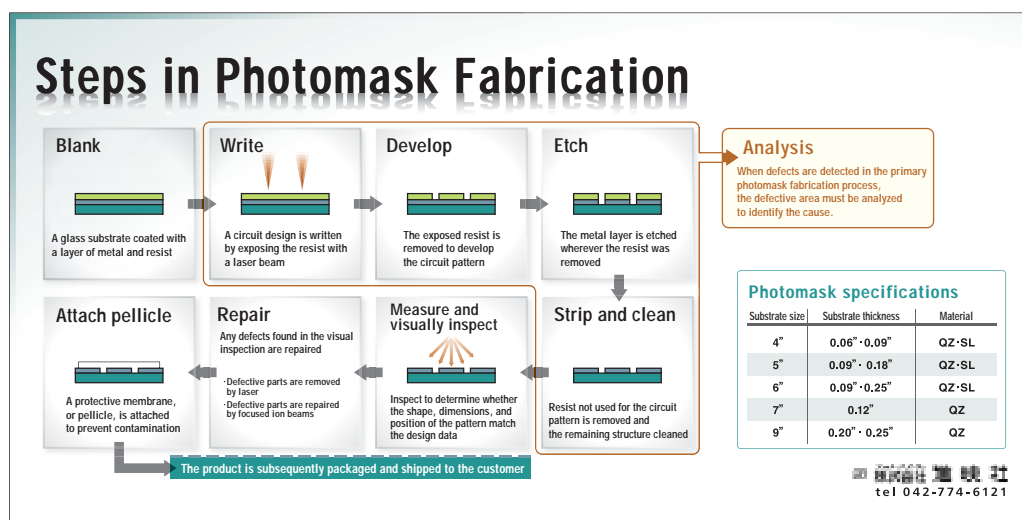
2. Product Lines

- Ultraprecision photomasks from 2", 4", 5", 6", 7", 8", and 9" up to a maximum size of 2 × 2.5 meters
- Ultraprecision photomasks for MEMS, thin-film integrated circuits, master integrated circuits, MPUs, package substrates, and electronic parts
- Photomasks for flat panel displays, such as flat-screen TVs
- Photomasks and lead frames for printed circuit boards

3. Photomask Technology

Shineisha is equipped with more than ten writing tools required to manufacture photomasks of various sizes, as well as inspection and repair systems. In addition to the VIOLD laser plotter, which we have used for some time, we recently added a production line to our Sagamihara plant in Kanagawa Prefecture for manufacturing high-resolution chrome masks. The production line was installed by the U.S. company Applied Materials, who purchased Etec Systems, and includes the CORE laser lithography tool. CORE employs an argon ion laser with a wavelength of 363.8 nm that is capable of writing lines as fine as 0.6μm with a line width precision of ±0.05μm.

Photomasks for MEMS having a line width greater than 3μm are written with the conventional VIOLD system, while high-resolutions masks with a finer line width are written using the CORE system, enabling us to provide more reasonable photomasks to MEMS companies that have typically used semiconductor reticles. We hope that you take advantage of our photomasks when developing and producing your MEMS devices.



Announcement

We would like to announce the recent appointment of Hisao Sakuta (President and CEO of Omron Corporation) to replace Tamotsu Nomakuchi (President and CEO of Mitsubishi Electric Corporation) as chairman of the Micromachine Center and chair of the BEANS Laboratory. We ask for your continued cooperation as we go forward.

The first address from the new director will be combined with his New Year's address and included in the first edition of the quarterly magazine MICRONANO of 2010.

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